

10/577069

Customer No. 42798

Attorney Docket No. 7372/88130

AP20 Rec'd PCT/PTO 24 APR 2006

APPLICATION DATA SHEET

Title:	METHOD FOR MANUFACTURING COMPOUND SEMICONDUCTOR SUBSTRATE
First Inventor:	Masahiko HATA
Address:	2-20-6, Ottominami Tsuchiura-shi, Ibaraki Japan
Residence:	Tsuchiura-shi, Ibaraki, Japan
Citizenship:	Japan
Second Inventor:	Yoshinobu ONO
Address:	6-14-6, Kinunodai, Yawara-mura Tsukuba-gun, Ibaraki Japan
Residence:	Tsukuba-gun, Ibaraki, Japan
Citizenship:	Japan
Third Inventor:	Kazumasa UEDA
Address:	1-393-271-203, Karasuyama Tsuchiura-shi, Ibaraki Japan
Residence:	Tsuchiura-shi, Ibaraki, Japan
Citizenship:	Japan
Assignee:	Sumitomo Chemical Company, Limited
Address:	27-1, Shinkawa 2-chome Chuo-ku, Tokyo 104-8260 Japan
Foreign Priority:	This Application is the National Phase of International Application No. PCT/JP2004/016186 filed October 25, 2004, and claims the priority from Japanese Application No. 2003-365736, filed October 27, 2003, the complete disclosures of which are incorporated herein by reference.